



Substitute Form PTO-1449 (Modified)		U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 17979-034US1	Application No. 10/562,257
Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR 1.98(b))		Applicant Shafer et al.		
		Filing Date December 4, 2006	Group Art Unit 2621	

U.S. Patent Documents

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
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	AB	2002/0163629	11/7/2002	Switkes et al.			
	AC	2004/0109237	6/10/2004	Epple et al.			
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	AE	6,809,794	10/26/2004	Sewell			
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	AAA	5,682,263	10/1997	Robb et al.			

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EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

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							Yes No
	APP	EP 1 491 956	12/29/2004	EPO			
	AQQ	WO 2004/057589	7/8/2004	WIPO			
	ARR	WO 2004/107048	12/9/2004	WIPO			English abstract
	ASS	JP 2000-58436	02/25/2000	Japan			X
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							Yes No
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	AAAA	WO 2005/059618	6/30/2005	WIPO			
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	AMMM	JP10-303114	11/13/1998	Japan			X
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	APPP	EP 1 489 462	12/22/2004	EPO			
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	ASSS	Dammel et al., "193 nm Immersion Lithography – Taking the Plunge", Journal of Photopolymer Science and Technology, vol. 17 no. 4, pp 587-607 (2004).
	ATTT	Kawata et al., "Fabrication of 0.2mm Fine Patterns Using Optical Projection Lithography With an Oil Immersion Lens", Japanese Journal of Applied Physics, Japan Society of Applied Physics, Tokyo, Japan, vol. 31 no. 12B, Part 1, December 1, 1992, pp 4174-4177.
	AUUU	Owa et al., "Immersion Lithography; its Potential Performance Issues", Proceeding of the SPIE, SPIE, Bellingham, VA, vol. 5040 no. 1, February 28, 2003, pp 724-733.

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Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
	AVVV	Lammers, "Doped water' could extend 193-nm immersion litho," <i>EETimes Online</i> , http://www.eetimes.com/showArticle.jhtml?articleID=18310517 , 2 pages (January 28, 2004).
	AWWW	Saurei et al., "Design of an autofocus lens for VGA 1/4-inch CCD and CMOS sensors," <i>SPIE International Symposium: Optical Systems Design</i> , St. Etienne, France, 1 page (2003)
	AXXX	J.A. Hoffnagle et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", <i>Journal of Vacuum Science & Technology B: Microelectronics Processing and Phenomena</i> , American Vacuum Society, New York, NY, Vol. 17, No. 6, November 1999 (199-11) pp 3306-3309.
	AYYY	Smith, Bruce, "Water-based 193nm Immersion Lithography", Online!, http://www.sematech.org/resources/litho/meetings/immersion/20040128/presentations/06%20rit20\$microstepper%20effortsSmith.pdf ., (January 28, 2004).

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